

## **REGULAR PAPER**

## Development of gas-injected pulsed plasma CVD method using Ar/C<sub>2</sub>H<sub>2</sub> mixed gas for ultra-high-rate diamond-like carbon deposition

To cite this article: Toru Harigai et al 2023 Jpn. J. Appl. Phys. 62 SL1013

View the <u>article online</u> for updates and enhancements.

## You may also like

- Effects of catalyst-generated atomic hydrogen treatment on amorphous silicon fabricated by Liquid-Si printing Hiroko Murayama, Tatsushi Ohyama, Akira Terakawa et al.
- <u>Strain analysis of plasma CVD graphene</u> for roll-to-roll production by scanning transmission electron microscopy and <u>Raman spectroscopy</u> Ryuichi Kato, Yoshinori Koga, Kiyoto Matsuishi et al.
- Control of plasma-CVD SiO<sub>2</sub>/InAlN interface by ultrathin atomic-layer-deposited Al<sub>2</sub>O<sub>3</sub> interlayer

  Masamichi Akazawa and Shouhei Kitajima